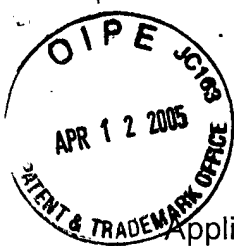


IFW



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE


Applicant: Michael Shu-Huan Wang, et al. Docket No: TI-34402
Serial No: 10/718,921 Conf. No: 2399
Examiner: Shantese L. McDonald Art Unit: 3723
Filed: 11/21/2003
For: CHEMICAL MECHANICAL POLISHING APPARATUS AND METHOD TO MINIMIZE
SLURRY ACCUMULATION AND SCRATCH EXCURSIONS

AMENDMENT UNDER 37 C.F.R. § 1.111

Commissioner For Patents
P.O. Box 1450
Alexandria, VA 22313-1450

MAILING CERTIFICATE UNDER 37 C.F.R. §1.8(a)

I hereby certify that the above correspondence is being deposited with the U.S. Postal Service with sufficient postage as First Class Mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on 4-8-05.


Ann Trent

Dear Sir:

Responsive to the Office Action mailed January 12, 2005, in connection with the above identified application, Applicants respectfully submit the following amendments and remarks.